

The opinion in support of the decision being  
entered today is not binding precedent of the Board.

Paper <sup>14</sup>

Richard E. Schafer  
Administrative Patent Judge  
Box Interference  
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Filed:  
10 September 2001

UNITED STATES PATENT AND TRADEMARK OFFICE

BEFORE THE BOARD OF PATENT APPEALS  
AND INTERFERENCES

MAILED

KOJI NOZAKI and EI YANO,  
Junior Party  
(Applications 09/015,287 and 09/080,530),

SEP 10 2001

PAT. & T.M. OFFICE  
BOARD OF PATENT APPEALS  
AND INTERFERENCES

v.

YASUNORI UETANI, HIROAKI FUJISHIMA  
and YOSHIKO MIYA,  
Junior Party  
(Application 09/014,915),

v.

HIDEO HADA, KAZUFUMI SATO  
and HIROSHI KOMANO  
Senior Party  
(Application 09/012,827).

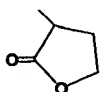
Patent Interference No. 104,664

REDECLARATION

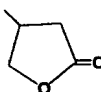
In light of the granting to the parties' preliminary motions, this interference is redeclared as  
follows:

## Count 2

A resist composition, comprising: an acid-sensitive film-forming polymer insoluble to an alkaline solution; a carboxyl group bonding to a side chain of said polymer's main chain, said carboxyl group having a protective group; and an additional acidic functional group bonding to a side chain of said polymer main chain, said acidic functional group having an acid-cleavable protective group; said carboxyl group having, as said protective group, a lactone structure represented by a member selected from the group consisting of formula A and formula B:



Formula A



Formula B

a photoacid generator causing a decomposition in response to an absorption of a radiation, said photoacid generator releasing an acid that causes a deprotection of said acid cleavable protective group in response to said decomposition; said resist composition becoming soluble to said alkaline solution after said acid cleavable protective group has caused said decomposition.

The claims<sup>1</sup> of the parties are:

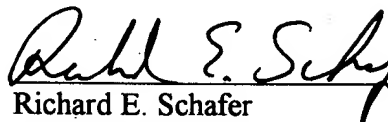
Hada	1-6, 8 and 10
Uetani	1-3, 5-6, 9-18
Nozaki Application 09/015,287	1-23
Nozaki Application 09/080,530	1-15

The claims of the parties which correspond to Count 1 are:

Hada	1-6, 8
Uetani	1-3, 5-6, 9-18
Nozaki Application 09/015,287	1-23
Nozaki Application 09/080,530	1-15

The claims of the parties which do not correspond to Count 1, and therefore are not involved in the interference, are:

Hada	10
Uetani	None
Nozaki Application 09/015,287	None
Nozaki Application 09/080,530	None

  
Richard E. Schafer  
Administrative Patent Judge

Date: 9/10/01  
Arlington, VA

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<sup>1</sup>

The reference is to claims as proposed to be amended.

cc (via Fax):

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## INTERFERENCE DIGEST

Interference No. 104,664

Paper No. 13

Name: Koji Nozaki et al.

Serial No.: 09/015,287

Patent No.

Title: Polymer compound for a chemical amplification resist and a fabrication process of a semiconductor device using such a chemical amplification resist

Filed: 01/29/98

Interference with Uetani et al. and Hada et al.

### DECISION ON MOTIONS

Administrative Patent Judge, \_\_\_\_\_ Dated, \_\_\_\_\_

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\_\_\_\_\_  
\_\_\_\_\_

### FINAL DECISION

Board of Patent Appeals and Interferences, favorable Dated, 12/13/01

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Court, \_\_\_\_\_ Dated, \_\_\_\_\_

### REMARKS

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